#### SUPPLEMENTARY INFORMATION

#### FOR

Frustrated amino functional group coupling with electric field makes CO<sub>2</sub> activation easier

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### **Computational method**

All calculations were performed using the Vienna ab initio simulation package (VASP) with the projector augmented wave formalism.[1] The electron-ion interactions were described by projected augmented wave (PAW) method with a kinetic energy cutoff of 420 eV. To correctly depict interaction caused by polarization and dispersion, van der Waals interactions was included in the D2 method of Grimme.

During the geometry optimization, the bottom two atomic layers was fixed and the remaining atoms were relaxed using a conjugate gradient method until the Hellmann-Feynman force on every atom could be smaller than 0.02 eV/Å. And the total energy converged to 1e-5 eV and the Brillouin zone was sampled with a 3×3×1 Monkhorst-Pack k point grid. The smearing method of second Methfessel-Paxton (MP) was applied with sigma parameter of 0.1 eV to determine how the partial occupancies.

The external electric field is actualized by adding an artificial dipole sheet defined by Neugebauer and Scheffler, which allows us to specify the direction and intensity of an electric field ranging from -0.6 V/Å to 0.6 V/Å perpendicular to the slab, i.e., alone z axis. The direction of applied electric field was perpendicular to the Cu(111), and the upward (downward) direction was defined as a positive (negative) one. Dipole corrections was turned on to avoid interactions between the periodically repeated images.

The adsorption energy of a molecular  $CO_2$  interaction with Cu(111) and  $CH_3NH_2$  is defined as follows:

#### Eb=E\_(Cu+CO<sub>2</sub>+CH<sub>3</sub>NH<sub>2</sub>)-E\_(Cu+CH<sub>3</sub>NH<sub>2</sub>)-E\_CO<sub>2</sub>

where  $\mathbf{E}_{(\mathbf{Cu}+\mathbf{CO}_{2}+\mathbf{CH}_{3}\mathbf{NH}_{2})$  denote the energy of theoptimized configurations of CO<sub>2</sub> in Cu(111) with CH<sub>3</sub>NH<sub>2</sub> under electric field,  $\mathbf{E}_{(\mathbf{Cu}+\mathbf{CH}_{3}\mathbf{NH}_{2})$  indicates the energy of the stable energy of Cu(111) with CH<sub>3</sub>NH<sub>2</sub> under corresponding electric field,  $\mathbf{E}_{\mathbf{CO}_{2}}$  represents the energy of the stable energy of CO<sub>2</sub> in the gas phase.

The charge density difference  $(\nabla \rho)$ , was obtained by subtracting electron density of CO<sub>2</sub> and Cu-CH<sub>3</sub>NH<sub>2</sub> in standalone state from the whole system:

#### $\nabla \rho = \rho(Cu - CH_3NH_2 - CO_2) - \rho(Cu - CH_3NH_2) - \rho(CO_2)$

Bader program[2] and PSI4 software [3] were used to analyze charge transfer and decompose energy contributions.



Stable structures under CH<sub>3</sub>NH<sub>2</sub> at flexible altitude and electric field

Figure SI-A. Optimized configurations of  $CO_2$  adsorbed on mircoenvironments of  $CH_3NH_2$  hanging at three heights 5.0Å, 6.0Å, 7.0Å above Cu(111) with flexible electric field ranging from -0.6V/Å to 0.6V/Å. unit is angstrom for distance and degree for angle.

### PSI energy decomposition analysis



Figure SI-B. Energy decomposition analysis as C-N distance changes.



**Density of state** 

Figure SI-C. left: Projected density of states of C in CO<sub>2</sub>, C and N in CH<sub>3</sub>NH<sub>2</sub> of optimized configurations of three attitudes CH<sub>3</sub>NH<sub>2</sub> above Cu(111) under 0.6 V/Å. right: Projected density of states of Cu and O at the same condition as figure a, where O1 is the close oxygen atoms in CO<sub>2</sub> to Cu(111), O2 is another oxygen atom in CO<sub>2</sub>. Cu is the closest copper atom to O1, Cu\* is a reference copper on the surface without direct interaction with CO<sub>2</sub>.

## PH<sub>2</sub> series of functional groups



Figure SI-D. Optimized configurations of  $CO_2$  under  $CH_3PH_2$  series chemical groups including electrondonor groups  $CH_3P(CH_3)_2(a)$ ,  $CH_3PHCH_3(b)$  and electron-acceptor groups where H in  $CH_3$  was replaced by F(d), hanging 6.0Å above Cu(111) surface under electric field strength 0.6V/Å.



## **OH** functional group

Figure SI-E. Optimized configurations of  $CO_2$  adsorbed on mircoenvironments of  $CH_3OH$  hanging at different height above Cu(111) with 0.6V/Å electric field.

# References

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(2) Yu, M.; Trinkle, D. R. Accurate and efficient algorithm for Bader charge integration. *The Journal of chemical physics* **2011**, *134*, 064111

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